In the Specification:

Paragraph 41 is amended as follows:

The multilayer stack 114 is a Bragg mirror having a composition and thickness so as to substantially reflect EUV radiation incident on the multilayer stack 114. Substantially reflecting EUV radiation incident on the multilayer stack 114 is defined herein as reflecting at least about 65% of the energy associated with said EUV radiation that is incident on the multilayer stack 114. The multilayer stack 114 may comprise alternating sheets of silicon (Si) and molybdenum (Mo). Said combination of Si and Mo provides a high peak reflectivity at an EUV source wavelength of 13.4 nm. The number of alternating sheets is application dependent and a representative number of such sheets is 80 sheets (i.e., 40 sheets of Si alternating with 40 sheets of Mo). The sheets may have a pitch (i.e., distance between two adjacent sheets) that is application dependent and a representative pitch is about 7 nm. The pitch may be a constant pitch or a variable pitch. The temperature at which the multilayer stack 114 is subjected to should be low enough (such as, inter alia, below 150 °C, depending on the multilayer stack 114 material composition) to prevent damage to the multilayer stack 114. The multilayer stack 114 may have other compositions than the aforementioned alternating sheets of Si and Mo, so long as the substantial reflectivity requirement is satisfied. The multilayer stack 114 may include a top layer, called a "capping layer," whose purpose is to protect the alternating sheets of the multilayer stack 114 from damage (e.g., from oxidation damage, corrosion damage, etc.) and also to enhance the reflectivity of the multilayer stack 114 with respect to the incident EUV radiation. The capping layer may comprise silicon or other material consistent with the multilayer stack 114 being able to substantially reflect EUV radiation incident thereon. The multilayer stack 114,

together with the substrate 112 on which the multilayer stack 114 is deposited, is called an "EUVL mask blank."